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Pulsed Laser Deposition for MEMS Device

Guest Editor:

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Message from the Guest Editor

Dear colleagues,

Pulsed laser deposition (PLD) is a promising technique for the growth of functional thin films because PLD enables the growth of stoichiometric and epitaxial thin film for complex materials. In this respect, PLD-grown thin films have been widely used for not only understanding fundamental properties of materials but also applying in various fields such as superconductor, mem-device, metalinsulator transition, and so on. Accordingly, this Special Issue seeks to recent advances in the thin film growth using PLD with its application to various fields, especially to modern electronic devices.

Dr. Sehun Seo Guest Editor













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Message from the Editor-in-Chief

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